



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of	:	Confirmation No. 9635
Satoshi MAEMORI et al.	:	Attorney Docket No. 2001_1300A
Serial No. 09/955,111	:	Group Art Unit 1752
Filed September 19, 2001	:	Examiner Sin J. Lee
POSITIVE-WORKING PHOTORESIST COMPOSITION AND PHOTSENSITIVE MATERIAL USING SAME		Mail Stop: AF

RESPONSE TO FINAL REJECTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Final Rejection dated September 7, 2005, the period for response having been extended for one month by the attached petition, please amend the present application as follows: